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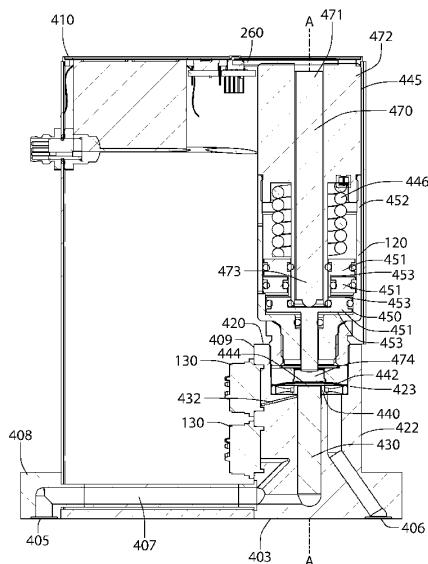


FIG. 11

(57) Abstract: Systems for processing articles are essential for semiconduc-
tor fabrication. These systems employ a variety of apparatuses for controlling
flow. In one implementation, an apparatus for controlling flow may utilize a
body having a flow path extending from an inlet to an outlet. A valve, a flow
restrictor, and a pressure sensor are operably coupled to the flow path. The
valve incorporates first and second actuators which enable control of mass
flow rates of fluid flowing through the flow path.

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